

Coaxial RuO₂-ITO nanopillars for transparent supercapacitor application

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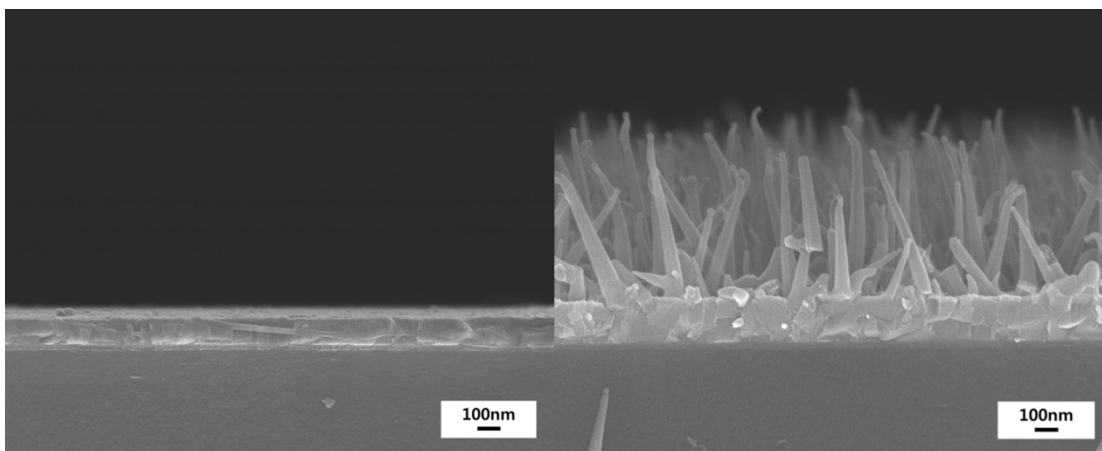


Figure S1. Cross-sectional FE-SEM images of the ITO film with a thickness of 140 nm (left) and ITO nanopillars (right) fabricated from ITO film by RF-magnetron sputtering.

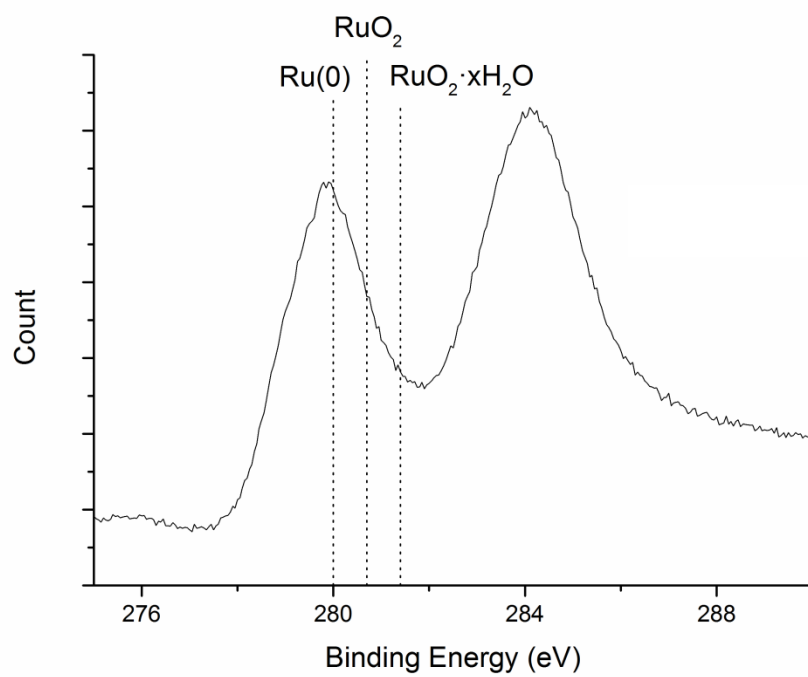


Figure S2. XPS spectra of Ru 3d for the hydrous RuO₂ deposits on ITO nanopillars by cathodic deposition at -0.8 V.

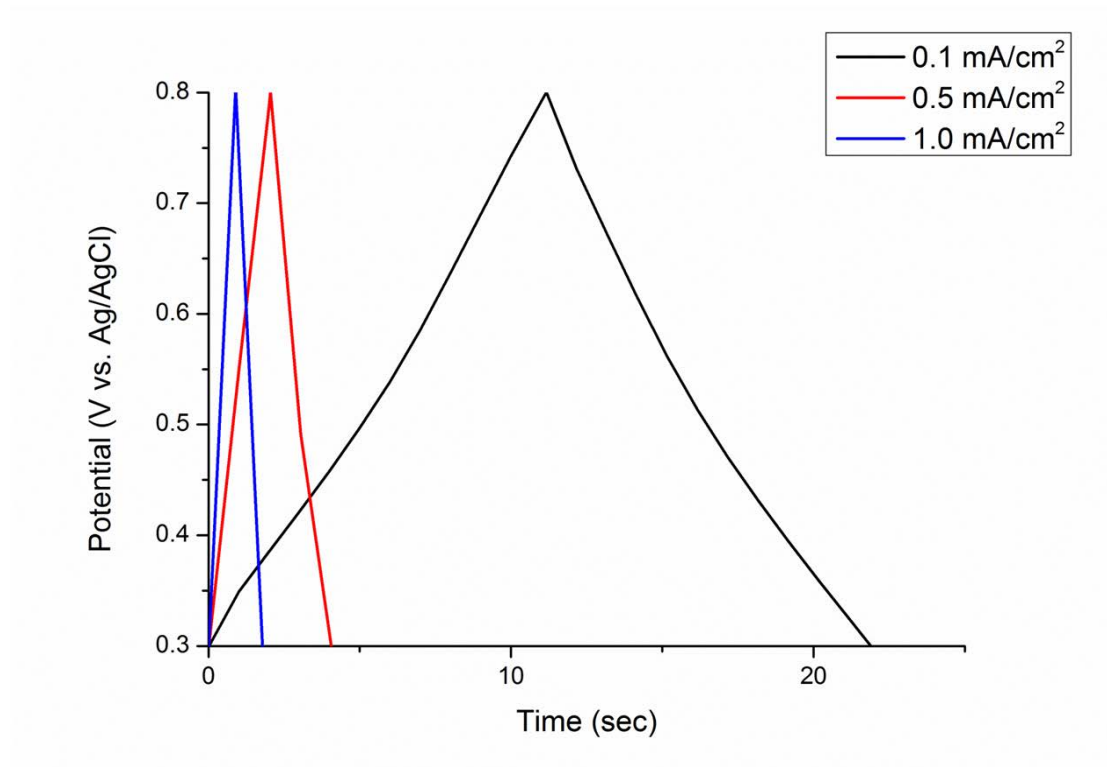


Figure S3. Charge-discharge curves at different constant current densities of 0.1, 0.5, and 1.0 mA/cm² for 30 cycle RuO₂ electrodeposited ITO coaxial (RuO₂-ITO) nanopillars.